

Tungsten Sputtering Target

Typical Specification Sheet · For preliminary RFQ discussion

Planning reference only. Illustrative values are not a batch CoA or guaranteed acceptance limits; order-specific requirements and actual batch documentation govern.

W	99.9550%	450 ppm	PASS
Material	Illustrative matrix	Illustrative impurities	Closed arithmetic

Reference product definition

Reference grade	3N5 nominal planning grade (99.95 wt%)
Order-specific scope	Geometry, finished dimensions, tolerances, bonding/backing, inspection and acceptance criteria are per approved drawing and quotation.

Closed illustrative composition model

The W balance and listed illustrative impurities form one closed mass-basis model. Basis: wt%, total mass basis.

Constituent	Illustrative wt%	Equivalent ppm	Role
W	99.9550	—	matrix balance
O	0.0150	150	illustrative typical impurity
C	0.0100	100	illustrative typical impurity
N	0.0050	50	illustrative typical impurity
Fe	0.0020	20	illustrative typical impurity
Ni	0.0020	20	illustrative typical impurity
Si	0.0020	20	illustrative typical impurity
Al	0.0020	20	illustrative typical impurity
Ca	0.0010	10	illustrative typical impurity
Mg	0.0010	10	illustrative typical impurity
Cu	0.0010	10	illustrative typical impurity
Other	0.0040	40	illustrative typical impurity
Total impurities	0.0450	450	arithmetic checked
COMPOSITION TOTAL	100.0000	—	PASS

ARITHMETIC VALIDATION: matrix 99.9550 wt% + illustrative impurities 0.0450 wt% = 100.0000 wt%. Individual impurity sum = 450 ppm. **ALL CHECKS PASS.**

Information to include in an RFQ

Target geometry and drawing/revision · finished dimensions and tolerances · required purity/composition basis · controlled impurities · planar or rotary configuration · bonding/backing requirement · quantity · inspection and document requirements.

Use this sheet only for early engineering discussion. Request an order-specific specification and the actual batch CoA before material acceptance or use.